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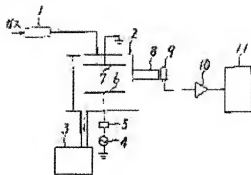
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(54) METHOD FOR CLEANING PLASMA TREATING DEVICE

(57)Abstract:

PURPOSE: To provide a method for cleaning plasma treating devices by which the availability of a plasma treating device can be improved and, at the same time, the reproducibility of the processability can be improved by making the treating chamber of the device cleanable without breaking the vacuum in the chamber after the plasma treatment of samples is completed in the chamber.

CONSTITUTION: When the plasma treatment of a prescribed number of samples is completed under a vacuum condition in a treating chamber 2, the samples are taken out from the chamber 2 and, after the gas remaining in the chamber 2 is discharged without opening the chamber 2 against the atmosphere, a cleaning gas is introduced into the chamber 2. Then the inside of the chamber 2 is cleaned with plasma by generating the plasma from the cleaning gas in the vacuum and completion of the cleaning is confirmed by monitoring the cleaned state of the inside.



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